

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of:    **CORNELIS PETRUS ANDREAS MARIE LUIJKX**  
                                 **VADIM YEVGENYEVICH BANINE**  
                                 **HAKO BOTMA**  
                                 **MARTINUS VAN DUIJNHOFEN**  
                                 **MARKUS FRANCISCUS ANTONIUS EURLINGS**  
                                 **HEINE MELLE MULDER**  
                                 **HANS MUIJDERMAN**  
                                 **CORNELIS JACOBUS VAN DUIJN**

Application No.:	TO BE ASSIGNED	Confirmation No:
Filed:	December 31, 2003	Group No.:
		Examiner
For:	OPTICAL ATTENUATOR DEVICE, RADIATION SYSTEM AND LITHOGRAPHIC APPARATUS THEREWITH AND DEVICE MANUFACTURING METHOD	

**Commissioner for Patents**  
**P.O. Box 1450**  
**Alexandria, VA 22313-1450**

**APPLICATION DATA SHEET**  
**37 C.F.R. § 1.76**

**BIBLIOGRAPHIC DATA**

**1. Applicant information**

First applicant: **CORNELIS PETRUS ANDREAS MARIE LUIJKX**  
Citizenship: The Netherlands  
Residence: Frans Halsstraat 30, NL-5684 AH Best, The Netherlands

Second applicant: **VADIM YEVGENYEVICH BANINE**  
Citizenship: The Netherlands  
Residence: Nierslaan 2, NL-5704 NK Helmond, The Netherlands

Third applicant: **HAKO BOTMA**  
Citizenship: The Netherlands  
Residence: Evertsenstraat 9, NL-5612 KP Eindhoven, The Netherlands

Fourth applicant: **MARTINUS VAN DUIJNHOFEN**  
Citizenship: The Netherlands  
Residence: Warande 8, NL-5752 AE Deurne, The Netherlands

Fifth applicant: **MARKUS FRANCISCUS ANTONIUS EURLINGS**  
Citizenship: The Netherlands  
Residence: Oosterbeekstraat 31, NL-5045 TH Tilburg, The Netherlands

Sixth applicant: **HEINE MELLE MULDER**  
Citizenship: The Netherlands/United States of America  
Residence: Kruisakker 60, NL-5625 SE Eindhoven, The Netherlands

Seventh applicant: **HANS MUIJDERMAN**  
Citizenship: The Netherlands  
Residence: Veldhoven, The Netherlands

Eighth applicant: **CORNELIS JACOBUS VAN DUIJN**  
Citizenship: The Netherlands  
Residence: Klaver 2, NL-5684 HZ Best, The Netherlands

## **2. Correspondence information**

Correspondence for this application should be addressed as follows:

Customer No.: 00909

## **3. Application information**

Title of Invention: OPTICAL ATTENUATOR DEVICE, RADIATION SYSTEM  
AND LITHOGRAPHIC APPARATUS THEREWITH AND  
DEVICE MANUFACTURING METHOD

Docket number assigned to this application: 081468-0307475

Total number of drawing sheets: 14

Type of application: Utility

Application is to be published. Suggested drawing figure for publication: FIGURE 2

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

## **4. Representative information**

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

**5. Assignee information**

The assignee(s) of this application is/are:

ASML NETHERLANDS B.V.

De Run 1110, NL-5503 LA Veldhoven, THE NETHERLANDS

Extent of interest of assignee in application: ENTIRE RIGHT, TITLE AND INTEREST

Date: **December 31, 2003**

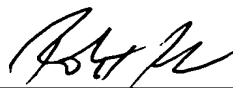
PILLSBURY WINTHROP LLP

P.O. Box 10500

McLean, VA 22102

Tel. No.: (703) 905-2159

Customer No.: 00909



---

Signature of Practitioner

Robert C. Perez

Reg. No.: 39328